INFORMATION DISCLOSURE CITATION Docket: 015559-288 Appln. No.: 10/620,119 Payed of 3 Pages Applicant: Thomas Wiegele et al. Group: 2874 Filed: July 15, 2003 U.S. PATENT DOCUMENTS Class Sub Document No. Date Name aminer 2003/0107794 06/2003 | Siekkinen et al. TML 6,525,864 02/2003 Gee et al. 09/2002 Herrmann 6,449,079 09/2001 Salatino et al. 6,291,317 M 5,923,995 07/1999 Kao et al. M 02/1998 Schubert et al. 5,721,162

FOREIGN PATENT DOCUMENT						Trans		
Examiner	Document No.	Date		Country	Class	Sub	Y	N
m	06-120336 (with English abstract)	04/1994	Japan	·				Х
m	08-106614 (with English abstract)	04/1996	Japan					Х

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

Graph of cure time vs. glass transition temperature for BCB (date unknown)
Applicants admit the status of this graph as prior art for the limited purpose of examination of this application, but otherwise reserve the right to challenge the status of this publication as prior art.

Statement by Applicants (including Attachment A)

M. Jenkins, et al., "Chemical and Structural Characterization of Silane Adhesion Promoting Films for Use in Microelectronic Packaging, Materials Research Society. Symp. Vol. 629, pp. FF5.12.1-FF5.12.6 (2000)

Examiner:

Date Considered: 05/2005

*Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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		F. Niklaus, et al., "Low-Temperature Wafer-Level Transfer Bonding," Journal of				
CATEMIE TO		Microelectromechanical Systems, Vol. 10, No. 4, pp. 525-531 (12/2001)				
M		F. Niklaus, et al., "Void-Free Full Wafer Adhesive Bonding," Department of Signals, Sensors and Systems, Royal Institute of Technology, Stockholm, Sweden (date unknown) Applicants admit the status of this publication as prior art for the limited purpose of examination of this application, but otherwise reserve the right to challenge the status of this publication as prior art.				
M		S.K. Sampath, et al., "Rapid MEMS Prototyping using SU-8, Wafer Bonding and Deep Reactive Ion Etching," IEEE (2001)				
W_		A. Jourdain, et al., "Investigation of the Hermeticity of BCB-Sealed Cavities for Housing (RF-)MEMS Devices," IEEE, pp. 677-680 (2002)				
m		T-K. Chou et al., "3D MEMS Fabrication Using Low-Temperature Wafer Bonding with Benzocyclobutene (BCB)," The 11 th International Conference on Solid-State Sensors and Actuators, Munch, Germany (6/2001)				
m		J. Neysmith et al., "A Modular, Chip Scale, Direct Chip Attach MEMS Package: Architecture and Processing," The International Journal of Microcircuits and Electronic Packaging, Vol. 23, No. 4, pp. 474-480 (2000)				
M		P.V. Dressendorfer, et al., "MEMS Packaging – Current Issues and Approaches," 2000 International Conference on High-Density Interconnect and System Packaging (2000)				
M		Product literature entitled "CYCLOTENE TM 4000 Series Advanced Electronic Resins (Photo BCB) – Processing Procedures for Cyclotene 4000 Series (Photo BCB Resins DS2100 Puddle Develop Process," CYCLOTENE TM Advanced Electronic Resins, by Dow (revised 5/03/1999)				
m	,	Product literature entitled "CYCLOTENE TM 4000 Series Advanced Electronic Resins (Photo BCB) – Processing Procedures for CYCLOTENE TM 4000 Series Photo BCB Resins – Immersion Develop Process," CYCLOTENE TM Advanced Electronic Resins, by Dow (revised 4/02/2001)				
m		Product literature entitled "Cure and Oxidation Measurements for Cyclotene Advanced Electronic Resins," CYCLOTENE TM Advanced Electronic Resins, by Dow (date unknown) Applicants admit the status of this publication as prior art for the limited purpose of examination of this application, but otherwise reserve the right to challenge the status of this publication as prior art.				
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CATEMIA TRA	G. Mittendorfer, et al., "Summary Study of BCB Coating Tests," by EVG (date unknown) Applicants admit the status of this publication as prior art for the limited purpose of examination of this application, but otherwise reserve the right to challenge the status of this publication as prior art.
m	"Tutorial 1 – Introduction to Flip Chi;p: What, Why, How," web page by Flip Chips Dot Com (date of first publication unknown). Applicants admit the status of this publication as prior art for the limited purpose of examination of this application, but otherwise reserve the right to challenge the status of this publication as prior art.
m	S. Renard, "Wafer level Surface Mountable Chip Size Packaging for MEMS and ICs," Micromachined Devices and Components VI, Proceedings of SPIE, Vol. 4176 (2000)
m	H.H. Gatzen, "Dicing challenges in microelectronics and micro electro-mechanical systems (MEMS)," Microsystem Technologies, 7, pp. 151-154 (2001)
Th	H.H. Gatzen, et al., "Advances in Dicing Wafers for Micro Electro-Mechanical Systems (MEMS)," Proceedings Volume 2, MICRO tec 2000, Hanover Germany (9/2000)
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